

Special Issue

Novel Applications of Plasma Techniques for the Environment

Message from the Guest Editor

The aim of this Special Issue of *Applied Sciences* is to provide a description of devices and processes related to plasma applications for the environment. Discharge plasmas comprise mixtures of photons, electrons, and ions, but may also contain neutral atoms and molecules.

The concept of plasma includes media with vastly different properties. Readers interested in this modern field of science and technology are invited to enjoy this new collection of articles, which will certainly stir the curiosity of both scientists and engineers interested in plasma applications for the environment. This Special Issue of *Applied Sciences* is remarkable in this period of change in the approach to environmental protection.

Guest Editor

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Message from the Editor-in-Chief

As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal Applied Sciences has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

Editor-in-Chief

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